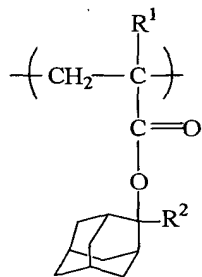


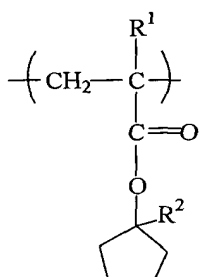
WHAT IS CLAIMED IS:

1. A radiation-sensitive resin composition comprising:

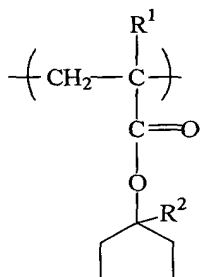
(A) a resin comprising at least two recurring units of the  
5 following formulas (1)-(6),



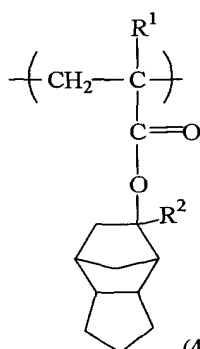
(1)



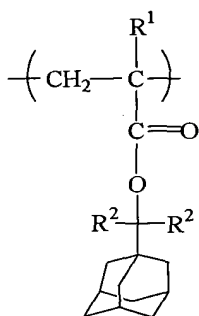
(2)



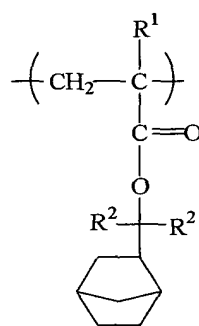
(3)



(4)



(5)



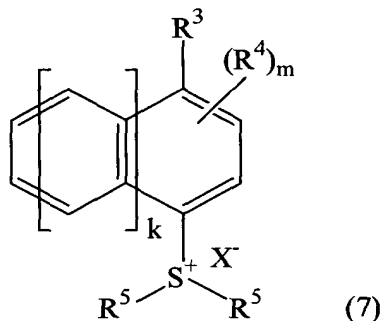
(6)

wherein R<sup>1</sup> represents a hydrogen atom or methyl group and R<sup>2</sup>  
represents a substituted or unsubstituted alkyl group having  
1-4 carbon atoms, two or more R<sup>2</sup> groups that may be present being  
10 either the same or different, in the total amount of 5-70 mol%,  
but each in the amount of 1-49 mol%, the resin being insoluble  
or scarcely soluble in alkali, but becoming easily soluble in  
alkali by the action of an acid, and

(B) a photoacid generator.

2. The radiation-sensitive resin composition according to claim 1, wherein the photoacid generator (B) is the compound shown by the formula (7),

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wherein R<sup>3</sup> represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1-10 carbon atoms, linear or branched alkoxy group having 1-10 carbon atoms, or linear or branched alkoxycarbonyl group having 2-11 carbon atoms, R<sup>4</sup> represents a linear or branched alkyl group having 1-10 carbon atoms, R<sup>5</sup> individually represents a linear or branched alkyl group having 1-10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R<sup>5</sup> groups bond to form a substituted or unsubstituted divalent group having 2-10 carbon atoms, k is an integer of 0 to 2, X<sup>-</sup> represents an anion represented by the formula R<sup>6</sup>C<sub>n</sub>F<sub>2n</sub>SO<sub>3</sub><sup>-</sup> (wherein R<sup>6</sup> represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10), and m is an integer of 1 to 10.

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3. The radiation-sensitive resin composition according

to claim 1, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

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4. The radiation-sensitive resin composition according to claim 1, wherein the resin (A) comprises at least two recurring units selected from the group consisting of the recurring units of the formulas (1)-(3).

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5. The radiation-sensitive resin composition according to claim 1, wherein the resin (A) comprises at least one recurring unit selected from the group consisting of the recurring units of the formulas (1)-(3) wherein  $R^2$  is a methyl group and at least one recurring units selected from the group consisting of the recurring units of the formulas (1)-(3) wherein  $R^2$  is other than the methyl group.

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6. The radiation-sensitive resin composition according to claim 1, wherein the resin (A) comprises at least one recurring unit of the formula (6) wherein  $R^2$  is a methyl group and at least one recurring unit selected from the group consisting of the recurring units of the formulas (1)-(3).

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